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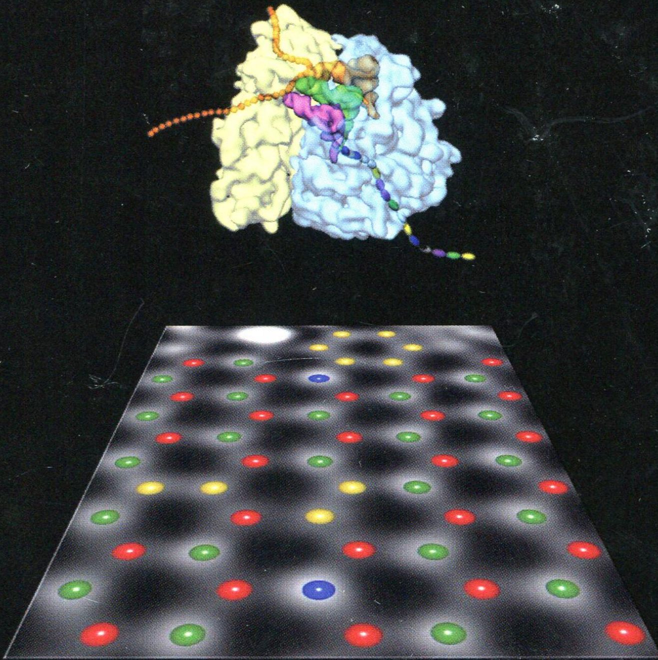
High-Resolution Electron Microscopy

FOURTH EDITION



JOHN C. H. SPENCE

High-Resolution Electron Microscopy

Fourth Edition

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Contents

Symbols and abbreviations xvii

1 Preliminaries 1
- 1.1 Elementary principles of phase-contrast TEM imaging 2
- 1.2 Instrumental requirements for high resolution 8
- 1.3 First experiments 10
- References 11

2 Electron optics 13
- 2.1 The electron wavelength and relativity 13
- 2.2 Simple lens properties 16
- 2.3 The paraxial ray equation 22
- 2.4 The constant-field approximation 24
- 2.5 Projector lenses 25
- 2.6 The objective lens 28
- 2.7 Practical lens design 29
- 2.8 Aberrations 31
- 2.9 The pre-field 37
- 2.10 Aberration correction 38
- References 43
- Bibliography 45

3 Wave optics 46
- 3.1 Propagation and Fresnel diffraction 47
- 3.2 Lens action and the diffraction limit 50
- 3.3 Wave and ray aberrations (to fifth order) 55
- 3.4 Strong-phase and weak-phase objects 61
- 3.5 Diffractograms for aberration analysis 63
- References 65
- Bibliography 66

4 Coherence and Fourier optics 67
- 4.1 Independent electrons and computed images 69
- 4.2 Coherent and incoherent images and the damping envelopes 70
- 4.3 The characterization of coherence 76
- 4.4 Spatial coherence using hollow-cone illumination 79
- 4.5 The effect of source size on coherence 81
- 4.6 Coherence requirements in practice 83
- References 86
- Bibliography 87

5 TEM imaging of thin crystals and their defects 88
5.1 The effect of lens aberrations on simple lattice fringes 89
5.2 The effect of beam divergence on depth of field 93
5.3 Approximations for the diffracted amplitudes 96
5.4 Images of crystals with variable spacing—spinodal decomposition and modulated structures 102
5.5 Are the atom images black or white? A simple symmetry argument 104
5.6 The multislice method and the polynomial solution 106
5.7 Bloch wave methods, bound states, and 'symmetry reduction' of the dispersion matrix 107
5.8 Partial coherence effects in dynamical computations—beyond the product representation. Fourier images 113
5.9 Absorption effects 115
5.10 Dynamical forbidden reflections 117
5.11 Relationship between algorithms. Supercells, patching 122
5.12 Sign conventions 125
5.13 Image simulation, quantification, and the Stobbs factor 126
5.14 Image interpretation in germanium—a case study 129
5.15 Images of defects and nanostructures 134
5.16 Tomography at atomic resolution—imaging in three dimensions 143
5.17 Imaging bonds between atoms 145
References 146

6 Imaging molecules: radiation damage 154
6.1 Phase and amplitude contrast 154
6.2 Single atoms in bright field 157
6.3 The use of a higher accelerating voltage 165
6.4 Contrast and atomic number 169
6.5 Dark-field methods 171
6.6 Inelastic scattering 174
6.7 Noise, information, and the Rose equation 177
6.8 Single-particle cryo-electron microscopy: tomography 180
6.9 Electron crystallography of two-dimensional crystals 188
6.10 Organic crystals 190
6.11 Radiation damage: organics and low-voltage EM 192
6.12 Radiation damage: inorganics 195
References 197

7 Image processing, super-resolution, and diffractive imaging 204
7.1 Through-focus series, coherent detection, optimization, and error metrics 204
7.2 Tilt series, aperture synthesis 210
7.3 Off-axis electron holography 211
7.4 Imaging with aberration correction: STEM and TEM 212
7.5 Combining diffraction and image data for crystals 215
7.6 Ptychography, Ronchigrams, shadow images, in-line holography, and diffractive imaging 219
7.7 Direct inversion from dynamical diffraction patterns 226
References 226

8 Scanning transmission electron microscopy and Z-contrast 233
8.1 Imaging modes, reciprocity, and Bragg scattering 233
8.2 Coherence functions in STEM 240
8.3 Dark-field STEM: incoherent imaging, and resolution limits 243
8.4 Multiple elastic scattering in STEM: channelling 249
8.5 Z-contrast in STEM: thermal diffuse scattering 251
8.6 Three-dimensional STEM tomography 257
References 260

9 Electron sources and detectors 264
9.1 The illumination system 265
9.2 Brightness measurement 268
9.3 Biasing and high-voltage stability for thermal sources 270
9.4 Hair-pin tungsten filaments 274
9.5 Lanthanum hexaboride sources 274
9.6 Field-emission sources 275
9.7 The charged-coupled device detector 276
9.8 Image plates 281
9.9 Film 282
9.10 Direct detection cameras 283
References 286

10 Measurement of electron-optical parameters 289
10.1 Objective-lens focus increments 289
10.2 Spherical aberration constant 291
10.3 Magnification calibration 293
10.4 Chromatic aberration constant 295
10.5 Astigmatic difference: three-fold astigmatism 295
10.6 Diffractogram measurements 296
10.7 Lateral coherence width 299
10.8 Electron wavelength and camera length 302
10.9 Resolution 303
10.10 Ronchigram analysis for aberration correction 306
References 312

11 Instabilities and the microscope environment 315
11.1 Magnetic fields 315
11.2 High-voltage instability 318
11.3 Vibration 319
11.4 Specimen movement 319
11.5 Contamination and the vacuum system 321
11.6 Pressure, temperature, and draughts 323
References 323

12 Experimental methods 324
12.1 Astigmatism correction 325
12.2 Taking the picture 326
12.3 Recording atomic-resolution images—an example 328

12.4 Adjusting the crystal orientation using non-eucentric specimen holders 335
12.5 Focusing techniques and auto-tuning 337
12.6 Substrates, sample supports, and graphene 340
12.7 Film analysis and handling for cryo-EM 343
12.8 Ancillary instrumentation for HREM 344
12.9 A checklist for high-resolution work 345
References 346

13 Associated techniques 348
13.1 X-ray microanalysis and ALCHEMI 348
13.2 Electron energy loss spectroscopy in STEM 357
13.3 Microdiffraction, CBED, and precession methods 363
13.4 Cathodoluminescence in STEM 372
13.5 Environmental HREM, imaging surfaces, holography of fields, and magnetic imaging with twisty beams 376
References 380

Appendices 388
Index 403